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PALL DEVELOPS NOVEL PURIFIER TO PROTECT OXYGEN ANALYZERS IN KEY CHIP MANUFACTURING PROCESSES

Low-temp RTP, ALD, PVD and CVD applications benefit from longer oxygen sensor life

East Hills, NY (July 13, 2005) – In a first-of-its-kind development, Pall Corporation today introduced a new purification technology to safeguard critical oxygen analyzers used in a number of semiconductor manufacturing processes, including emerging applications. The new Gaskleen®-SP purifier assembly extends the life of oxygen analyzers, helping boost equipment uptime and ensure long-term analyzer accuracy.

Device manufacturers use oxygen analyzers to monitor exhaust gases in a number of processes that are especially sensitive to oxygen impurities, including newer atomic layer deposition (ALD) and low-temperature rapid thermal processing (RTP) silicide applications, as well as chemical vapor deposition (CVD) and physical vapor deposition (PVD). Gaskleen-SP purifier assemblies work by removing harmful gaseous impurities that interfere with the electrode material and zirconium oxide (ZrO_2) sensor inside the oxygen analyzer. Typically, customers must calibrate these sensors every few months, but Gaskleen-SP purifier assemblies allow users to reduce the number of required calibrations by as much as seven times over a one-year period.

“For the first time, the industry has a reliable technology to extend the life of oxygen analyzers with zirconium oxide sensors,” said Steve Chisolm, president of Pall Microelectronics. “This is a significant technology development because oxygen analyzers are increasingly important as more and more customers adopt advanced-generation processes such as lower-temperature RTP, which requires more stringent control of oxygen impurities.”

Developed using Pall's core, in-house membrane expertise, Gaskleen-SP purifier assemblies mark the latest addition to the company's line of purification products. The Gaskleen-SP purifier assembly is a unique combination of a metal catalyst and Pall's Ultramet-L™ stainless steel filter technology. The metal catalyst reacts with harmful gaseous contaminants to reduce or eliminate impurities that cause drift in the oxygen analyzer readings and degradation of the electrode performance.

Pall Microelectronics is the global leader in filtration, separations and purification technologies for the microelectronics industry. It supports the semiconductor, data storage, fiber optic, advance display and materials markets with a comprehensive suite of contamination control solutions for chemical, gas, water, chemical mechanical polishing and photolithography processes.

About Pall Corporation

Pall Corporation (NYSE: PLL) is the global leader in the rapidly growing field of filtration, separations and purification. Pall's business is organized around two broad markets: Life Sciences and Industrial. The Company provides leading-edge products to meet the demanding needs of customers in biotechnology, pharmaceuticals, transfusion medicine, semiconductors, water purification, aerospace and broad industrial markets. Total revenues for fiscal 2004 were $1.8 billion. The Company is headquartered in East Hills, New York with extensive operations throughout the world. Further information is available at www.pall.com.

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